

## AMENDMENT TO THE CLAIMS

Claims 1-8 (canceled).

Claim 9 (previously presented) A liquid processing apparatus as claimed in Claim 10, wherein

the ejecting orifices are formed so as to eject the processing liquid in a substantially fan-shaped pattern.

Claim 10 (currently amended) A liquid processing apparatus comprising:

a processing container ~~formed so as to surround~~ surrounding a processing chamber in which one or more substrates to be processed are accommodated; and

a nozzle for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle having ejecting orifices to eject the processing liquid in ~~the form of a plane~~ which is substantially parallel with the substrates;

wherein the substrates consist of a plurality of substrates whose processing surfaces to be processed thereon are arranged generally parallel with each other;

wherein the ejecting orifices are juxtaposed with the plural substrates;

wherein the substrates are arranged so as to be rotatable about substantial centers thereof;

wherein the nozzle is formed so as to eject the processing liquid obliquely to the processing surfaces of the plural substrates and to substantial centers of the substrates;

wherein each of the substrates is in the form of a circular plate; and

wherein the nozzle is formed so as to eject the processing liquid against ~~each~~ the processing surface of the substrates so that a width of the plane-ejected processing liquid is generally equal to the diameter of the substrate, on the processing surface.

Claim 11. (currently amended) A liquid processing apparatus comprising:

a processing container ~~formed so as to surround~~ surrounding a processing chamber in which one or more substrates to be processed are accommodated; and

a nozzle for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle having ejecting orifices to eject the processing liquid in ~~the form of a plane~~ which is substantially parallel with the substrates;

wherein the substrates consist of a plurality of substrates whose processing surfaces to be processed thereon are arranged generally parallel with each other;

wherein the ejecting orifices are juxtaposed with the plural substrates;

wherein the substrates are arranged so as to be rotatable about substantial centers thereof;

wherein the nozzle is formed so as to eject the processing liquid obliquely to the processing surfaces of the plural substrates and to substantial centers of the substrates;

wherein the nozzle comprises:

a nozzle body provided with a plurality of pedestals formed corresponding to the substrates to be processed; and

nozzle members attached to the plural pedestals, the nozzle members having the ejecting orifices formed therein; and

wherein the pedestals ~~are formed to~~ incline so that the nozzle members can eject the processing liquid obliquely to the processing surfaces of the substrates.

Claim 12. (previously presented) A liquid processing apparatus as claimed in Claim 10, wherein

the nozzle has a nozzle body having the ejecting orifices formed therein, the ejecting orifices being inclined so as to eject the processing liquid obliquely to the processing surfaces of the substrates.

Claim 13. (previously presented) A liquid processing apparatus as claimed in Claim 10, wherein the ejecting orifices comprise:

a plurality of main ejecting orifices arranged so as to correspond to the plural substrates respectively; and

extra ejecting orifices arranged further outside of the outermost ones of the main ejecting orifices.

Claim 14. (previously presented) A liquid processing apparatus as claimed in Claim 10 or 11, wherein the nozzle comprises:

a first nozzle, and

a second nozzle,

wherein the first nozzle and the second nozzle are separated from each other in the circumferential direction of the substrates, the first nozzle having a plurality of first ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural

substrates to be processed, and the second nozzle having a plurality of second ejecting orifices to eject the processing liquid to alternately-positioned ones of the plural substrates except the alternately-positioned substrates charged by the first nozzle.

Claim 15. (previously presented) A liquid processing apparatus as claimed in Claim 10 or 11, wherein the ejecting orifices are arranged in a space above a horizontal plane including central axes of the substrates to be processed.

Claim 16. (previously presented) A liquid processing apparatus as claimed in Claim 10, wherein the processing container includes a lower portion which is formed to have an inner face with an inclination intersecting the horizontal direction at an angle more than 5 degrees.

Claim 17. (previously presented) A liquid processing apparatus as claimed in Claim 10, wherein the nozzle has an inside nozzle passage providing the ejecting orifice with the processing liquid, a sectional shape of the inside nozzle passage being rectangular.

Claim 18. (previously presented) A liquid processing apparatus comprising:

- a wafer holding member for holding a plurality of wafers;
- a circular plate on which the wafer holding member is built;
- a processing container for accommodating the circular plate and the wafer holding member therein, the container having an inner surface facing the circular plate; and

an ejecting orifice formed on the inner surface for ejecting a processing fluid towards a surface of the circular plate facing the inner surface of the processing container.

Claims 19 and 20 (canceled).

Claim 21. (currently amended) A liquid processing apparatus comprising:

a processing container ~~formed so as to surround~~ surrounding a processing chamber in which one or more substrates to be processed are accommodated, the substrates consisting of a plurality of substrates whose processing surfaces to be processed thereon are arranged generally parallel with each other and so as to be rotatable about substantial centers thereof; and

a nozzle for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle is formed so as to eject the processing liquid obliquely to the processing surfaces of the plural substrates ~~and also~~ to make the processing liquid come into contact with substantial centers of the substrates, the nozzle having ejecting orifices to eject the processing liquid in ~~the form of~~ a plane, the ejecting orifices being juxtaposed with respect to the plural substrates;

wherein the ejecting orifices are located relative to the position of the substrates so that in plan view the ejecting orifices do not overlap with the substrates, ~~and so that~~ whereby processing liquid adhered to ~~the~~ an ejecting orifice of the orifices does not drip down onto the substrates.

Claim 22. (currently amended) ~~A liquid processing apparatus according to claim 18,~~

A liquid processing apparatus comprising:

a wafer holding member for holding a plurality of wafers;

a circular plate on which the wafer holding member is built;

a processing container for accommodating the circular plate and the wafer holding member therein, the container having an inner surface facing the circular plate; and

an ejecting orifice formed on the inner surface for ejecting a processing fluid towards a surface of the circular plate facing the inner surface of the processing container,

wherein the processing fluid is a cleaning liquid.

Claim 23. (currently amended) ~~A liquid processing apparatus according to claim 18,~~

A liquid processing apparatus comprising:

a wafer holding member for holding a plurality of wafers;

a circular plate on which the wafer holding member is built;

a processing container for accommodating the circular plate and the wafer holding member therein, the container having an inner surface facing the circular plate; and

an ejecting orifice formed on the inner surface for ejecting a processing fluid towards a surface of the circular plate facing the inner surface of the processing container,

wherein the processing fluid is a drying fluid.

Claim 24. (currently amended) A liquid processing apparatus comprising:

a processing container ~~formed so as to surround~~ surrounding a processing chamber in which one or more substrates to be processed are accommodated, the substrates consisting of a plurality of substrates whose processing surfaces to be processed thereon are arranged generally parallel with each other and so as to be rotatable about substantial centers thereof, each of the substrates is in the form of a circular plate;

a nozzle for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle being formed so as to eject the processing liquid obliquely to the processing surfaces of the plural substrates ~~and also~~ to make the processing liquid come into contact with substantial centers of the substrates, the nozzle having ejecting orifices to eject the processing liquid in ~~the form of~~ a plane, the ejecting orifices being juxtaposed with respect to the plural substrates; and

wherein the ejecting orifices are ~~formed and~~ located so that the processing liquid is ejected against each processing surface of the rotating substrates in such a way that a width of the plane-ejected processing liquid is generally equal to a radius of the circular substrate, on the processing surface.

Claim 25. (currently amended) ~~A liquid processing apparatus according to claim 24,~~

A liquid processing apparatus comprising:

a processing container surrounding a processing chamber in which one or more substrates to be processed are accommodated, the substrates consisting of a plurality of substrates whose processing surfaces to be processed thereon are arranged generally parallel with each other and so as to be rotatable about substantial centers thereof, each of the substrates is in the form of a circular plate;

a nozzle for supplying the substrates with a processing liquid thereby to carry out a liquid process, the nozzle being formed so as to eject the processing liquid obliquely to the processing surfaces of the plural substrates to make the processing liquid come into contact with substantial centers of the substrates, the nozzle having ejecting orifices to eject the processing liquid in a plane, the ejecting orifices being juxtaposed with respect to the plural substrates; and

wherein the ejecting orifices are ~~formed and~~ located so that the processing liquid is ejected against each processing surface of the rotating substrates in such a way that a width of the plane-ejected processing liquid is generally equal to a radius of the circular substrate, on the processing surface,

wherein the circular substrates are rotating so that a direction of ~~rejecting~~ ejected liquid is opposite to a moving direction of a peripheral part of the rotating circular substrate in an area where processing liquid comes into contact with the surface of the rotating circular substrate.